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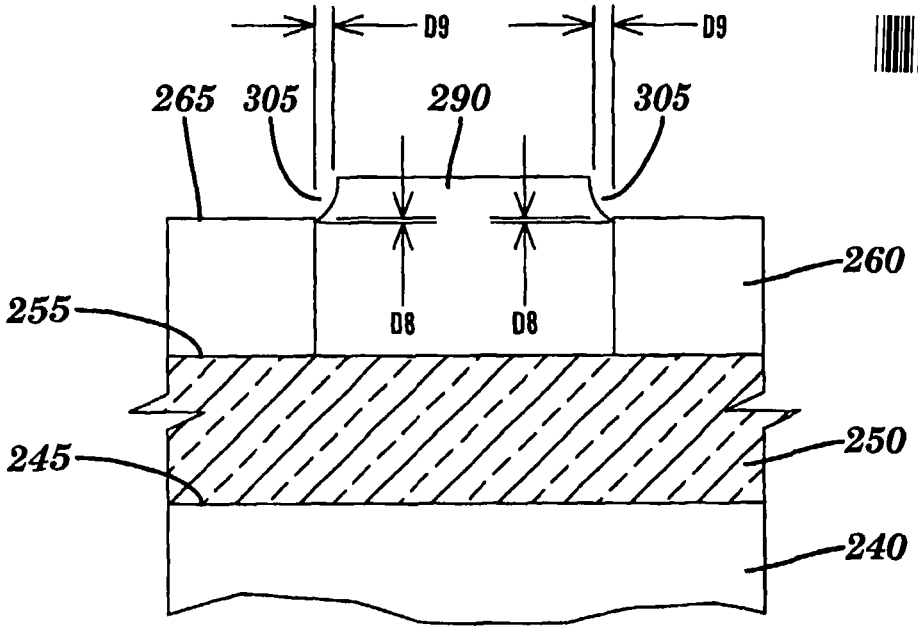
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(54) Title: METHOD FOR LIMITING DIVOT FORMATION IN POST SHALLOW TRENCH ISOLATION PROCESSES



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(57) Abstract: A method for limiting divot (305) formation in shallow trench isolation structures. The method includes: providing a trench (285) formed in a silicon region (260) with a deposited oxide (290); oxidizing a top layer of the silicon region (260) to form a layer of thermal oxide (302) on top of the silicon region (260); and selectively etching the thermal oxide (302) with respect to the deposited oxide (290).

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